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Chemical Process Modelling and Simulation

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Message from the Guest Editor

Modeling is a tool for understanding reality. We should never forget that the model is always just a projection of the real system so the reliability of the model should be quantified before it is applied in a practical problem solution. In modern chemical industry processes, modeling and simulation are a crucial pillar of day-to-day operations from design to maintenance and control of chemical process technologies. Today, the modeling task in the chemical industry often requires dynamic process modeling and simulation to follow the transient behavior of the system. Next to this, to obtain more information about the real system, we need more complex models than earlier, which makes it possible to identify that hidden capacity in process units which can improve the performance of the whole system. As model complexity is increasing, the numerical solution methods should be improved in order to solve models with sufficient precision.

All work related to chemical process modeling and simulation is welcome in this Special Issue to offer insight to the future readers into the current state of this wide topic.









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Message from the Editor-in-Chief

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